

NIL Industrial Day (May 11-12, 2020) - Program

May 11, 2020 ~ NIL Industrial Day
(part 1)

Organizer:  

10:00 - 11:00 Registration / Networking and Exhibition

11:00 - 12:00 Session I - Industrial NIL Manufacturing: Success Stories I

- 11:00 Teck Lee Chee, Moveon Technologies Pte Ltd, (SGP)
A Novel Method for Scalable Fabrication of Diffractive Optics Elements Via Nanoimprint Lithography
- 11:20 Sonny Vo, Leia Inc., (USA)
Using NanoImprint Lithography to achieve a robust Diffractive Lightfield BackLighting (DLBTM) for interactive holograms
- 11:40 Hoyoung Song, YNG Inc., (KOR)
NIL Technology for mass Production of pseudo random MLA and its various applications
- 12:00 Edwin Wolterink, Anteryon International BV, (NL)
Replication - key technology for future optical devices

12:20 - 14:00 Lunch and Networking and Exhibition

14:00 - 15:00 Session II - NIL Process Supply Chain: Industrial Partners

- 14:00 Berthold Lange, SCHOTT AG, (GER)
SCHOTT RealView™ Enabling High-Performance Augmented Reality Waveguides
- 14:20 Jan Klein / Arne Schleunitz / Manuel Thesen, micro resist technology GmbH, (GER)
Optical and photonic architectures? – Materials are the key!
- 14:35 Thanner Christine, EV Group, (AUT)
300mm SmartNIL – Challenges and Opportunities
- 14:50 Samuli Siitonen, Nanocomp Oy Ltd, (FIN)
UV-R2R NIL manufactured micro structured light guides for display application
- 15:05 Motohiko Tsuchiya, Scivax Corp., (JPN)
Quality of Nano Foundry Service

15:25 - 16:30 Coffee Break and Networking and Exhibition

16:30 - 17:30 Session III - NIL Process Development: Industrial Partners

- 16:30 Michael Hornung / Florian Schlachter, AMO GmbH, (GER)
NIL for Applications in Optics and Automotive
- 16:45 Boris Vratzov, NT&D - Nanotechnology and Devices GmbH, (GER)
Nanotechnology and Devices, UV-NIL enhanced Nanotechnology
- 17:00 Theodor Nielsen, NIL Technology ApS, (DEN)
Advanced Optical Components
- 17:15 Lars Dittrich, 5microns GmbH, (GER)
UV-NIL on non-planar surfaces – current challenges

Networking Dinner Event

NIL Industrial Day (May 11-12, 2020) - Program

May 12, 2020 ~ NIL Industrial Day
(part 2)

Organizer:  

09:00 - 09:30 Networking and Exhibition

09:30 - 10:30 Session IV - Future Applications of NIL

- 09:30 Moon Kyu Kwak, Kyungpook National University, (KOR)
Large area technology of NIL and its bio-inspired applications
- 09:45 Michael Mühlberger, PROFACTOR GmbH, (AUT)
A Step&repeat UV-Nanoimprinting as a versatile tool in the Nanoimprint process chain
- 10:00 Simon Drieschner, SÜSS MicroTec Lithography GmbH, (GER)
Highly efficient beam shaping elements using SMILE imprint technology and hybrid polymers
- 10:15 Jochen Zimmer, Nanoscribe GmbH, (GER)
Microfabrication of prototypes and masters by two-photon grayscale lithography

10:30 - 11:30 Coffee Break and Networking and Exhibition

11:30 - 12:30 Session VI - Industrial NIL Manufacturing: Success Stories II

- 11:30 Ismo Vartiainen, Dispelix Oy, (FIN)
Hunt for the holy grail in AR using NIL
- 11:50 David Kallweit, CSEM, (SUI)
Multilevel Nanosteel Technology for brand protection and decoration
- 12:10 Pia Harju / Nicolaus Hettler, CDA GmbH, (GER)
Challenges of mass-producing nano-patterns
- 12:30 Bradley Williams, Moxtek Inc., (USA)
Volume Manufacturing of Full Wafer Nanoimprint on Wire Grid Polarizers

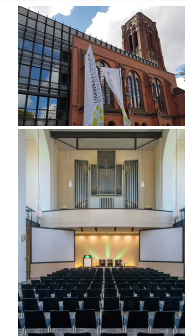
12:50 - 15:00 Lunch and Networking and Exhibition

15:00 Fare-well

End of NIL ID 2020

Location:
Umweltforum
Pufendorfstr. 11
10249 Berlin

Local organizer:
micro resist technology GmbH
Köpenicker Straße 325
12555 Berlin - Germany
www.microresist.com



Commercial exhibition:
Day 1 - 10:00 - 17:30
Day 2 - 09:00 - 15:00

Registration form and participation fees incl. commercial exhibition will be made available within one week by end of February the latest – we will inform separately!